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**(54) MOVING STAGE FOR IMPRINT LITHOGRAPHY**

pressing force can be applied to the resist.

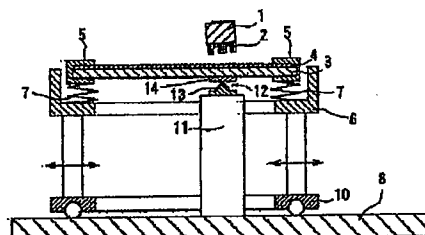
**(57) Abstract:**

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(a)

**PROBLEM TO BE SOLVED:** To enable uniform pressing of a mold against the surface of a specimen when a slant adjustment mechanism is attached on the sample side and the sample is moved by using a moving mechanism.

**SOLUTION:** A strut 11 is fixed at an almost center of a surface plate 8 having a flat surface, and a pivot 12 is fixed on an upper end surface of the strut 11, as the slant adjustment mechanism. A moving stage 6 is fixed on the moving mechanism 10 which moves on the plane of the surface plate, a sample-holding member 5 is retained by the moving stage 6 via elastic members 7, and a silicon substrate 3 which has a resist 4 on the surface is held by the sample-holding member 5. The mold 2 is arranged directly above the pivot 12 so as to be movable vertically, and the moving mechanism 10 is moved in such a manner that the surface of the resist to which the mold 2 is to be transferred is positioned directly below the mold 2. When the mold is pressed against the resist at a prescribed position, the elastic members 7 are transformed so that the mold and silicon substrate 3 become in parallel with each other in the case that both of them are slanted relatively. As a result, a uniform



(b)

